

CLAIMS

What is claimed is.

1 1. A process of forming a memory device, comprising:
2 forming a first topology over a substrate;
3 forming a subsequent topology over the first topology;
4 forming a first memory structure at the first topology; and
5 forming at least one subsequent memory structure at a corresponding at least one
6 subsequent topology.

1 2. The process according to claim 1, wherein the memory device includes a
2 ferroelectric memory device.

1 3. The process according to claim 2, wherein forming at least one subsequent
2 memory structure further includes:
3 forming a second topology;
4 forming a second memory structure at the second topology;
5 forming an interlayer dielectric (ILD) layer over the second memory structure;
6 forming a third topology above the ILD layer ; and
7 forming a third memory structure at the third topology.

1 4. The process according to claim 2, wherein forming at least one subsequent
2 memory structure further includes:
3 forming a second topology;

4 forming a second memory structure at the second topology, wherein the second
5 memory structure is formed comprising:

6 forming a ferroelectric layer over the first memory structure;

7 forming a conductive layer over the layer;

8 planarizing the conductive layer; and

9 patterning the conductive layer to form a third electrode; and

10 forming an interlayer dielectric (ILD) layer over the second memory structure;

11 forming a third topology above the ILD layer ; and

12 forming a third memory structure at the third topology.

1 5. The process according to claim 2, wherein forming a first memory structure
2 further includes:

3 forming a first electrode over the substrate;

4 forming a first memory layer over the first electrode; and

5 forming a second electrode over the first memory layer.

1 6. The process according to claim 2, wherein forming a first memory structure and
2 forming a subsequent memory structure further includes:

3 forming a first electrode over the substrate;

4 forming a first memory layer over the first electrode;

5 forming a second electrode over the first memory layer;

6 forming a second memory layer over the second electrode; and

7 forming a third electrode over the second memory layer.

7. A process of forming a ferroelectric polymer memory device, comprising:
 forming a first topology above a substrate;
 forming a subsequent topology over the first topology;
 forming a first ferroelectric polymer memory structure at the first topology; and
 forming at least one subsequent ferroelectric polymer memory structure at a
 corresponding at least one subsequent topology.

8. The process according to claim 7, wherein forming a subsequent ferroelectric
 polymer memory structure further comprises:
 forming a second topology;
 forming a second ferroelectric polymer memory structure at the second topology;
 forming an interlayer dielectric (ILD) layer over the second ferroelectric polymer
 memory structure;
 forming a third topology above the ILD layer ; and
 forming a third ferroelectric polymer memory structure at the third topology.

9. The process according to claim 7, wherein forming a subsequent ferroelectric
 polymer memory structure further comprises:
 forming a second topology;
 forming a second ferroelectric polymer memory structure at the second topology,
 wherein the second ferroelectric polymer memory structure is formed comprising:

forming a ferroelectric polymer layer over the first ferroelectric polymer
memory structure;
forming a conductive layer over the ferroelectric polymer layer;
planarizing the conductive layer; and
patterning the conductive layer to form a third electrode; and
forming an interlayer dielectric (ILD) layer over the second ferroelectric polymer
memory structure;
forming a third topology above the ILD layer ; and
forming a third ferroelectric polymer memory structure at the third topology.

10. The process according to claim 7, wherein forming a first ferroelectric memory
structure further comprises:

forming a first electrode over the substrate;
forming a first ferroelectric memory layer over the first electrode; and
forming a second electrode over the first ferroelectric memory layer.

11. The process of forming a memory device according to claim 7, wherein forming a
first ferroelectric polymer memory structure and forming a subsequent ferroelectric polymer
memory structure further comprises:

forming a first electrode over the substrate;
forming a first ferroelectric polymer memory layer over the first electrode;
forming a second electrode over the first ferroelectric polymer memory layer;

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8 forming a third ferroelectric oxide memory structure at the third topology.

1 15. The process according to claim 13, wherein forming a subsequent ferroelectric
2 oxide memory structure further comprises:

3 forming a second topology;

4 forming a second ferroelectric oxide memory structure at the second topology,

5 wherein the second ferroelectric oxide memory structure is formed comprising:

6 forming a ferroelectric oxide layer over the first ferroelectric oxide
7 memory structure;

8 forming a conductive layer over the ferroelectric oxide layer;

9 planarizing the conductive layer; and

10 patterning the conductive layer to form a third electrode; and

11 forming an interlayer dielectric (ILD) layer over the second ferroelectric oxide
12 memory structure;

13 forming a third topology above the ILD layer ; and

14 forming a third ferroelectric oxide memory structure at the third topology.

1 16. The process according to claim 13, wherein forming a first ferroelectric oxide
2 memory structure further comprises:

3 forming a first electrode over the substrate;

4 forming a first ferroelectric oxide memory layer over the first electrode; and

5 forming a second electrode over the first ferroelectric oxide memory layer.

1 17. The process of forming a memory device according to claim 13, wherein forming
2 a first ferroelectric oxide memory structure and forming a subsequent ferroelectric oxide memory
3 structure further comprises:

- 4 forming a first electrode over the substrate;
- 5 forming a first ferroelectric oxide memory layer over the first electrode;
- 6 forming a second electrode over the first ferroelectric oxide memory layer;
- 7 forming a second ferroelectric oxide memory layer over the second electrode; and
- 8 forming a third electrode over the second ferroelectric oxide memory layer.

1 18. The process according to claim 13, wherein forming a ferroelectric oxide memory
2 structure comprises forming a layer selected from chemical vapor deposition, spin-on deposition,
3 and physical vapor deposition.

1 19. A ferroelectric memory device comprising:
2 a first topology disposed over a substrate;
3 a first ferroelectric structure disposed in the first topology; and
4 a subsequent topology disposed over the first topology, and a subsequent
5 ferroelectric structure disposed in the subsequent topology.

1 20. The ferroelectric memory device according to claim 19, wherein the first
2 ferroelectric structure and a subsequent ferroelectric structure further comprise:
3 a first electrode disposed over the substrate;
4 a first ferroelectric polymer layer disposed over the first electrode;

5 a second electrode disposed over the first ferroelectric polymer layer;
6 a second ferroelectric polymer layer disposed over the second electrode; and
7 a third electrode disposed over the second ferroelectric polymer layer.

1 21. The ferroelectric memory device according to claim 20, wherein the electrodes
2 have a width that is a minimum feature of a photolithography technology, selected from 0.25
3 micron, 0.18 micron, 0.13 micron, and 0.11 micron.

1 22. The ferroelectric memory device according to claim 20, wherein the first
2 ferroelectric structure and a subsequent ferroelectric structure further comprise:
3 a first electrode disposed over the substrate;
4 a first ferroelectric oxide layer disposed over the first electrode;
5 a second electrode disposed over the first ferroelectric oxide layer;
6 a second ferroelectric oxide layer disposed over the second electrode; and
7 a third electrode disposed over the second ferroelectric oxide layer.

1 23. The ferroelectric memory device according to claim 21, wherein the electrodes
2 have a width that is a minimum feature of a photolithography technology, selected from 0.25
3 micron, 0.18 micron, 0.13 micron, and 0.11 micron.

1 24. A system, comprising:
2 a processor;
3 a ferroelectric memory system coupled to the processor;

1 28. The system according to claim 24, wherein the processor comprises logic in a
2 memory controller, and wherein the ferroelectric memory system comprises a die in a memory
3 module.

1 29. The system according to claim 24, wherein the ferroelectric memory system
2 comprises a chip in a chipset.